

INSCOOP: Intégration de Nanofils III-V sur SOI pour Connexions Optiques sur Puce

ANR-P2N 2011

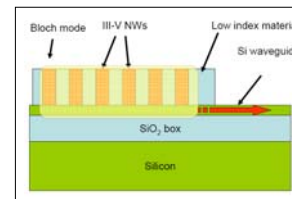
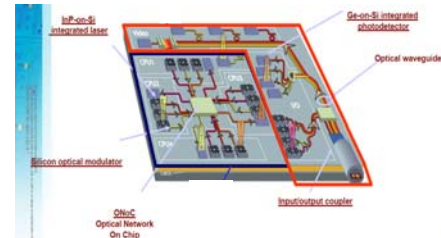


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Contexte: la Photonique Silicium

- Interconnexions optiques sur puces
- Intégration monolithique d'une microsource optique sur Si par la « technologie nanofils »
- Couplage de la microsource à base de NFs avec un guide d'onde Si sur SOI

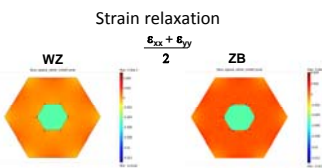
➔ vers des « nanofils photoniques »



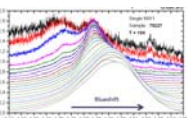
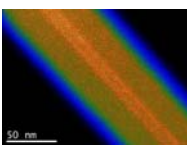
Microsource optique à base de NFs formant aussi une cavité résonante de type PhC dont le mode optique va se coupler avec celui d'un guide d'onde Si sur SOI

LPN

Core-shell NWs, NWs on Si(111)
Structural and optical properties
Strain and Growth modeling

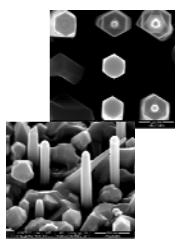


Core-shell InAsP/InP NWs on InP

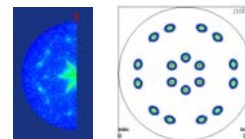


PL spectroscopy on single InP NW

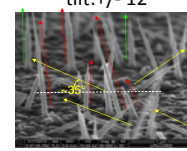
InP NWs in holes in SiO2/Si(111)



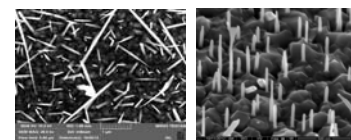
XRD pole figure for NWs growth directions



80% of vertical InP NWs on STO(001): tilt: +/- 12°



InP NWs with In droplet catalyst



Foton

Exciton modeling

-DFT atomistic modeling
Deformation potential
Band-offsets

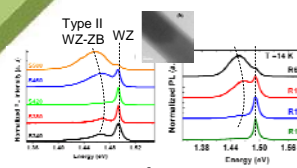
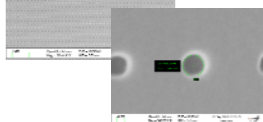
ZB offset	V _{LDA} (eV)	V _{LDA} (eV)	Ev (eV)	VBO (eV)
[111]	InAsP	InP		
InAs	-9.24	-8.82	0.06	0.39
InP	-9.48	-10.05	0.65	
WZ offset	V _{LDA} (eV)	V _{LDA} (eV)	Ev (eV)	VBO (eV)
InAsP	InP			
InAs	-9.23	-8.72	0.08	0.31
InP	-9.46	-9.88	0.69	

LTM

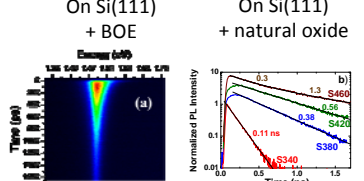
Site-controlled catalyst on SOI waveguide
Au-free catalyst



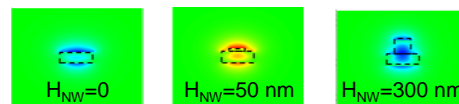
Holes in SiO2/Si(111)
D=50 nm, p=200 nm



PL of InP NWs (function of Tc and V/III ratio)



Exciton life time of InP NWs by TRPL



Resonator and coupling modeling: 3D FDTD

Useful E.M. Field is mainly located in the foot of the NW

CEA-Leti-Dopt

SOI waveguide
NWs integration

Production scientifique (publications, brevets)

J. Even, L. Pedesseau, C. Hajaoui, C. Katan and J.-M. Jancu, Non-linear electro-elastic coupling in non-centrosymmetric materials, *Journal of Physics: Conference Series*, 2012.
 J. Even, L. Pedesseau, C. Hajaoui, C. Katan and J.-M. Jancu, Theory, modelling and computational methods for semiconductors, (TMCS III), Jan 18, 2012 - Jan 20, 2012, Leeds, United Kingdom.
 J.C. Harmand, F. Jabeen, L. Liu, G. Patriarche, K. Gauthron, P. Senellart, D. Elvira, A. Beveratos, InP1-xAsx quantum dots in InP nanowires: a route for single photon emitters, *The 17th International Conference on MBE (ICMBE 2012)*, September 23-28, 2012, Nara, Japan. To be published in *J. Cryst. Growth*.
 K. Naji, H. Dumont, G. Saint-Girons, J. Penuelas, G. Patriarche, M. Hocevar, V. Zwiller, M. Gendry, Growth of vertical and defect free InP nanowires on SrTiO3(001) substrate and comparison with growth on silicon, *Journal of Crystal Growth*, 101-104 343 (2012)
 H. Khmisi, K. Naji, M.H. Hadj Alouane, N. Chauvin, C. Bru-Chevallier, B. Ilahi, G. Patriarche, M. Gendry, InAs/InP nanowires grown by catalyst assisted molecular beam epitaxy on silicon substrates, *Journal of Crystal Growth* 45-50 344 (2012)
 N. Chauvin, M.H. Hadj Alouane, R. Anufriev, H. Khmisi, K. Naji, G. Patriarche, C. Bru-Chevallier, M. Gendry, Growth temperature dependence of exciton lifetime in wurtzite InP nanowires grown on silicon substrates, *Applied Physics Letters* 011906 100 (2012)
 R. Anufriev, M. H. Hadj Alouane, N. Chauvin, H. Khmisi, K. Naji, A. Belarouci, B. Ilahi, H. Maaref, G. Patriarche, M. Gendry and C. Bru-Chevallier, InAs/InP nanowire quantum rodesemitting in the 1.55 μm telecommunication window on silicon substrate, 6th NGW, 4-6 June, 2012, Saint-Petersbourg, Russia

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